16.1 A 22nm 4Mb 8b-Precision ReRAM Computing-in-Memory Macro with 11.91 to 195.7TOPS/W for Tiny Al Edge Devices

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Battery-powered tiny-AI edge devices require large-capacity nonvolatile compute-in-memory (nvCIM), with multibit input (IN), weight (W), and output (OUT) precision to support complex applications, high-energy efficiency (EF_{MAC}), and short computing latency (t_{AC}) for multiply-and-accumulate (MAC) operations. Due to the low read-disturbfree voltage of nonvolatile memory (NVM) devices and the large parasitic load on the bitline, most existing Mb-level nvCIM macros use a current-mode read scheme [1-5] and only achieve a low IN-W precision (binary to 4b).

As shown in Fig. 16.1.1, the above requirements impose serious challenges: (1) Long input latency due to input schemes using serial WL pulse-counts [6] or a fully-decoded WL pulse-width; (2) Limited system-level accuracy for high-precision MAC operations due to small signal margin caused by process variation and pattern-dependent bitline current under various input bit configurations; and (3) Large power consumption in readout circuit due to DC current consumption in the current-summation of partial MAC values (pMACV) with respective place values. To overcome these challenges we developed: (1) An asymmetric group-modulated input (AGMI) scheme, in which a 8b-input is split into 3 sub-groups (2b-3b-3b) to reduce computing latency, while maintaining sufficient signal margins for the most significant bits (MSBs); (2) A weighted current-to-voltage signal stacking (WCVSS) converter to translate the dataline current of partial MAC operations into voltage-mode signals with respective place values; and (3) A hybrid-precision voltage-mode readout scheme with voltage-mode sense amplifier (VSA) to reduce energy consumption and shorten the $t_{\rm AC}$ for multibit MAC readout operations, while maintaining the sensing margin for MSBs.

The proposed 22nm 4Mb ReRAM macro, fabricated using foundry SLC 1T1R ReRAM technology, is the first nvCIM macro supporting 8b-input and 8b-weight MAC operations. Among silicon-verified nvCIMs, it achieved the fastest $t_{\rm AC}$ (4.9-14.8ns) and best EF_{MAC} (195.7-11.91TOPS/W) with precision from binary IN-W to 8bIN-8bW-14bOUT. Our nvCIM macro delivers MAC operations comprising 4 sets of 8bIN and 8bW in the channel direction. Note that 4 accumulations per column (bitlines/BL) provide sufficient signal margin against process variation. 8bW data is stored in 8 ReRAM cells on the same row (wordline/WL) across 8 columns in 2's complement format. Each set of columns comprises memory cells, column multiplexors (column MUX), a WCVSS converter, a CVSA, and digital shift-and-add circuits (DSAC).

Figure 16.1.2 shows the operation of AGMI on one column for the LSB of weights (W[0]), in which an 8b-input (IN[7:0]) is split into 3 grouped signals (IN[7:6], IN[5:3], and IN[2:0]), generating three sequential WL pulses (WLP2~WLP0) with corresponding pulse-widths. The pulse-width of WLP2 (T_{WLP2}) includes one precharge and BL current-development phase (P-BLPD, T_{BL-PD}) and up to 3 time-units ($T_{U-WCVSS1}$) for WCVSS operations. Each pulse-width of WLP1 and WLP0 ($T_{WLP1} = T_{WLP0} = T_{BL-PD} + 7 \cdot T_{U-WCVSS2}$) is includes 1 T_{BL-PD} and up to 7 $T_{U-WCVSS2}$. Note that $T_{U-WCVSS1}$ is $T/3 \times 100$ longer than $T_{U-WCVSS2}$ be ensure sufficient signal margin for the pMACV of MSBs (IN[7:6]) of inputs. In the WLP2 phase, the BL is precharged to the read voltage and then each activated memory cell (MC) (at WL=1) generates a memory cell current (I_{MC}), based on stored weight data (HRS or LRS). The BL current (I_{BL}) is the sum of the four I_{MC} representing the partial MAC result of 2b-input, 1b-weight, and 4 accumulations. In the WLP1 and WLP0 phases, each I_{BL} is the partial MAC result of 3b-input, 1b-weight, and 4 accumulations.

Figure 16.1.3 shows the operation of WCVSS: comprising of three current-scaling transistors (P1, P2, P3), two current-mirror inhibitors (PS1, PS2), two bias PMOS (BP0, BP1), four switches (SW0, SW1, SW2, SW3), two initial transistors (N0, N1), and two capacitors for voltage stacking ($C_{\rm C}$, $C_{\rm S}$). In the WLP2 phase, N1 is on (S1=1) to keep node STACK at 0V, while SW0 is on to build the P1-P2 current-mirror circuit for down-scaling the dataline current ($I_{\rm DL}$) to $I_{\rm WDL0}$ (=0.5- $I_{\rm DL}$) with a scaling ratio of 0.5. Here, EN1=1 and SW0 is turned on up to 3 times to sample $I_{\rm WDL0}$ and then charge the node SUM connected to capacitor $C_{\rm C}$ and the input capacitor ($C_{\rm O}$) of VSA. The voltage at node SUM ($V_{\rm SUM-P2}$, maximum value is 8/9· $V_{\rm D0}$) is determined by $I_{\rm WDL0}$ sampled during the input phase. At the end of the WLP2 phase, VSA reads out the $V_{\rm SUM-P2}$ and turns on N0 (S0=1)

to reset C_0 and C_C to 0V. In the WLP1 phase, the generation of voltage at node SUM (V_{SUM-P1}) is similar to that of WLP2 phase, but with up to 7 SW0/EN1 pulses to sample I_{WDL0} and no readout operation at the end. In the WLP0 phase, SW1 is off, while SW3 is on to downscale I_{DL} through current-mirror pairs P1-P3 with a 1/16 scaling ratio, resulting I_{WDL1} = 1/16· I_{DL} . Here, EN2=1 and SW2 is turned on up to 7 times to sample I_{WDL1} and charge the node STACK connected to capacitors C_C and C_S , which make node STACK has matching capacitance at node SUM. Then, I_{WDL1} charges capacitor C_S to generate stacking voltage (V_{STACK} , maximum value is 1/9· V_{DD}) at node STACK. The value of V_{STACK} is simultaneously coupled to node SUM through capacitor C_C , such that the V_{SUM-P0} of WLP0 is the sum of V_{SUM-P1} and V_{STACK} . At the end of the WLP0 phase, VSA reads out the V_{SUM-P0} .

Figure 16.1.4 shows the hybrid-precision voltage-mode readout scheme with VSA. The $V_{\text{SUM-P2}}$ resulting from the WCVSS of the WLP2 phase is divided into 16 levels for full-precision sensing. The single VSA is activated twice (SAEN=1) at the end of the WLP2 phase to read $V_{\text{SUM-P2}}$ and generate a 4b digital output (SAOUT1[3:0]) for the pMACV result of $IN_0[7:6]xW_0[0]+IN_1[7:6]xW_1[0]+IN_2[7:6]xW_2[0]+IN_3[7:6]xW_3[0]$. At the end of WLP0 phase, the same VSA is activated twice to read $V_{\text{SUM-P0}}$ with reduced-precision of 4b (full-precision is 8b) and generate a 4b digital output (SAOUT2[3:0]) for the pMACV result of $IN_0[5:0]\cdot W_0[0]+IN_1[5:0]\cdot W_1[0]+IN_2[5:0]\cdot W_2[0]+IN_3[5:0]\cdot W_3[0]$. The 1st-level of DSAC (L1-DSAC) combine SAOUT1[3:0] and SAOUT2[3:0] to generate a 6b pMACV (DSACout0[5:0]) for $IN_0[7:0]\cdot W_0[0]+IN_1[7:0]\cdot W_1[0]+IN_2[7:0]\cdot W_2[0]+IN_3[7:0]\cdot W_2[0]$. The 2st-level of DSAC (L2-DSAC) combines 8 DSACout of 8 computing columns (DSACout7 - DSACout0 for W[7:0]) with place value (DSACout7[5:0]·(-128) + DSACout6[5:0]·(64) + ... + DSACout0[5:0]·(1)) to output a 14b DOUT (DOUT[13:0]) for the MAC operation of 8bIN-8bW-4Accumulations.

Figure 16.1.5 shows the performance of the proposed schemes. Under 8b-input, the proposed AGMI scheme reduces computing latency by 5.59-54.25×, compared to previous serial WL pulse-counts or the fully-decoded WL pulse-width schemes extended to 8b-input. This work has achieved a much higher signal margin for MSBs (with full precision) and LSBs (with reduced precision) of pMACVs compared to those of previous WL pulse-counts and WL pulse-width input schemes to achieve high macro-level read yield, which considers the resistance variation and pattern-dependent variation in signal values. Compared to previous work [5], this work improved EF_{MAC} by 1.66× under 4bIN-4bW mode with 1024 operations.

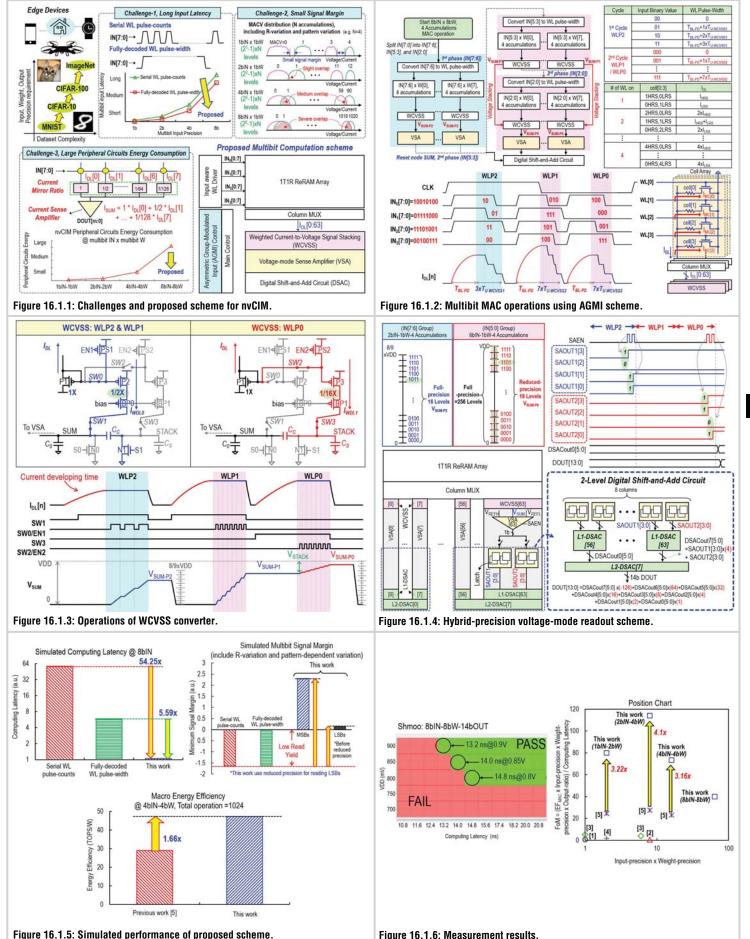
Figure 16.1.6 shows the measurement results from a 22nm 4Mb ReRAM nvClM macro fabricated using foundry ReRAM devices. The shmoo test for 8bIN-8bW-14bOUT confirmed a 14.8ns $t_{\rm AC}$ at a 0.8V V_{DD}. The measured EF_{MAC} was 47.26TOPS/W at 4bIN-4bW-10bOUT and 11.91TOPS/W at 8bIN-8bW-14bOUT. Compared to previous work [5], despite having twice the memory capacity, this work improved the FoM (EF_{MAC} × Input-precision × Weight -precision × Output-ratio / Computing latency) by 3.16-4.1× for binary up to 4bIN-4bW configurations. Figure 16.1.7 shows a die photo and summary table.

Acknowledgement:

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ISSCC 2021 PAPER CONTINUATIONS

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